

## **SUPPLEMENTARY DATA**

**Improved electrochemical properties of morphology-controlled titania/titanate nanostructures prepared by in-situ hydrothermal surface modification of self-source Ti substrate for high-performance supercapacitors**

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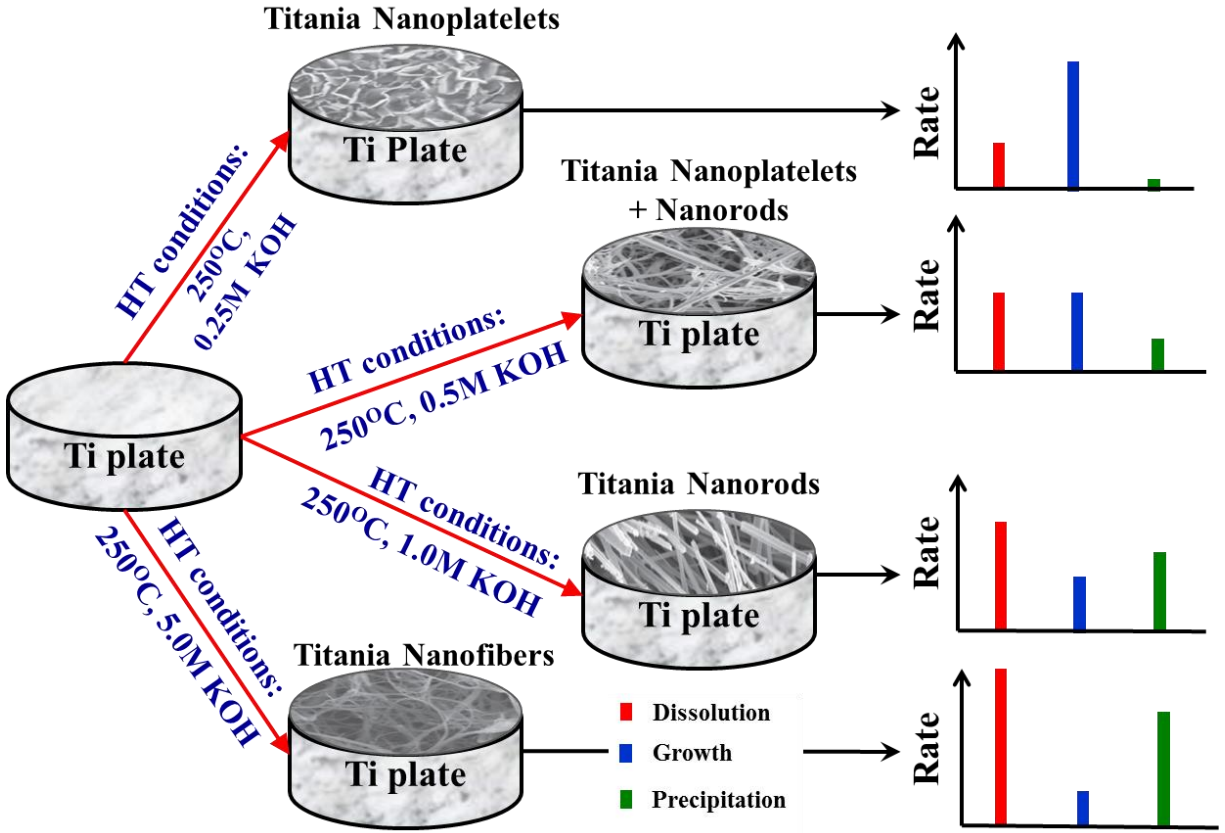
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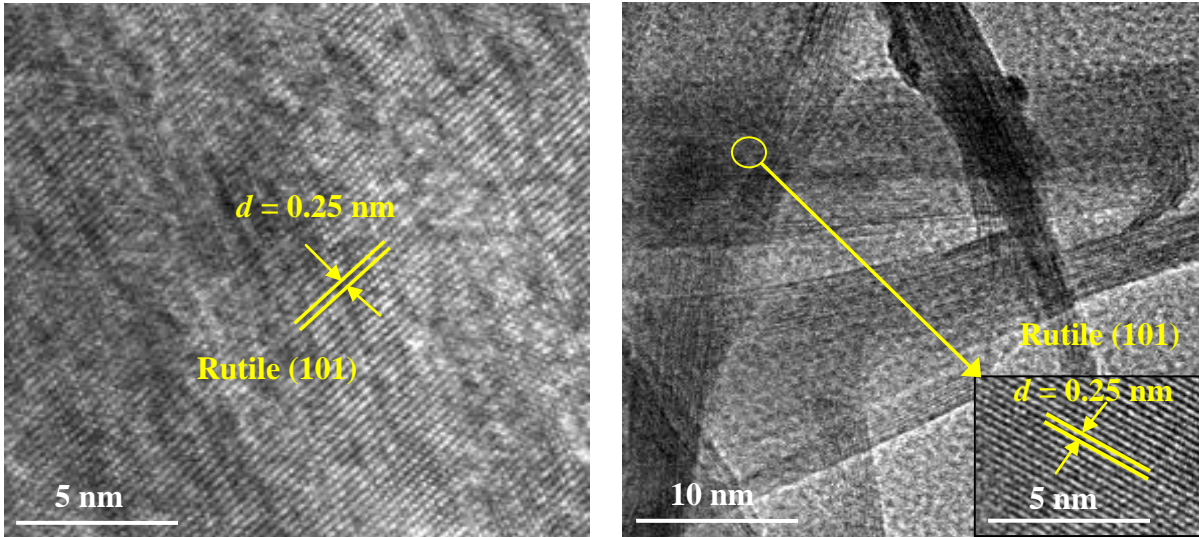
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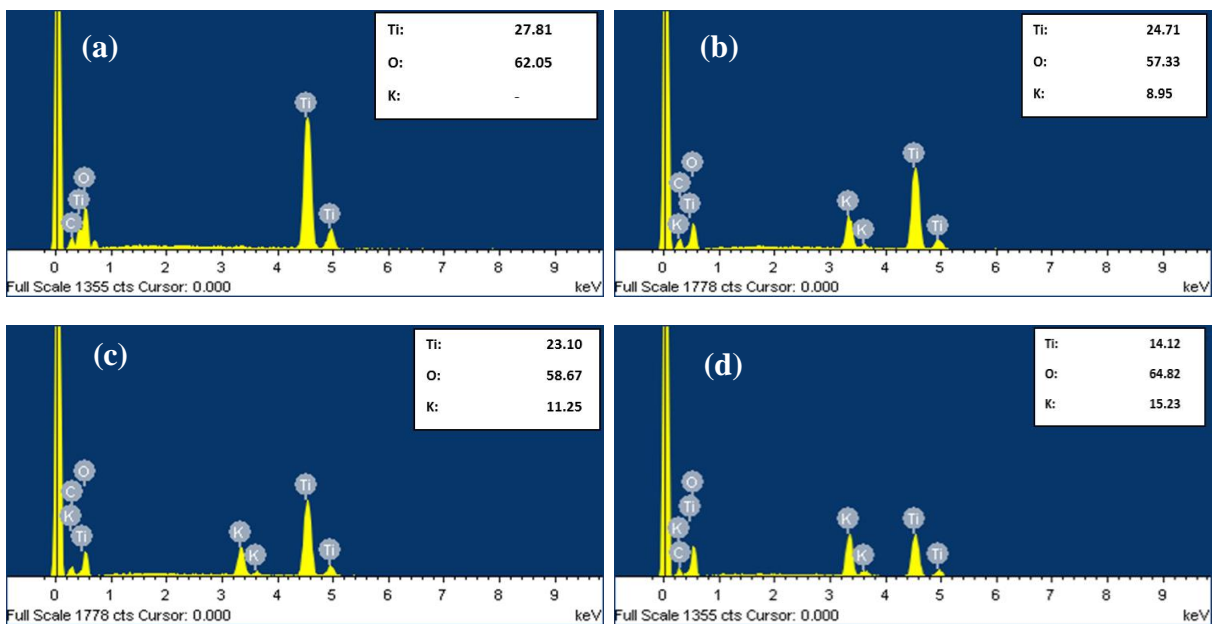
**Figure S1:** Schematic and pictorial representation of the hydrothermal synthesis of various titania nanostructures on the self-source Ti substrate under different KOH concentrations. Right-hand panel describes the relative dissolution, growth and precipitation rates of  $\text{TiO}_2$  on the Ti substrate as a function of KOH concentrations.

**Table S1:** A comparison of the  $2\theta$ -values of different diffraction peaks observed in the XRD data (Fig. 2b) with the 1999 JCPDS-ICDD File. Also  $d$ -values of Rutile titania for (110) and (101) planes obtained from Fig. 3 and Fig. S2 are compared with 1999 JCPDS-ICDD File.

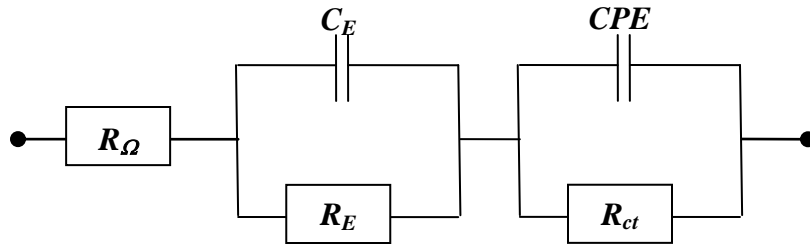
Peak origin		$2\theta_{\text{EXPT}}$ (deg.) (From Fig. 2b)	$2\theta_{\text{JCPDS}}$ (1999 JCPDS-ICDD File)	1999 JCPDS File Card #
TiO (110)		35.6	35.9	12-0754
Rutile TiO <sub>2</sub>	(101)	36.8	36.2	78-1510
	(202)	76.6	76.7	
Anatase TiO <sub>2</sub>	(200)	48.0	48.1	84-1286
	(105)	53.6	53.9	
	(220)	70.7	70.3	
Ti		40.1	40.2	05-0682
		63.2	63.0	
		77.5	77.3	
K-Titanate		11.6	11.5	74-0275
		24.4	24.6	
		25.5	25.6	
		29.6	29.8	
Rutile TiO <sub>2</sub> (From TEM micrographs)		$d_{110 \text{EXPT}} = 0.33 \text{ nm}$ (from Fig. 3)	$d_{110 \text{JCPDS}} = 0.324 \text{ nm}$	78-1510
		$d_{101 \text{EXPT}} = 0.25 \text{ nm}$ (from Fig. S2)	$d_{101 \text{JCPDS}} = 0.248 \text{ nm}$	



**Figure S2:** HRTEM micrographs of the interior of (a) titania platelet, (b) titania nanorods. The lattice spacing matches with the Rutile (101) planes with  $d$ -value around 0.25 nm.



**Figure S3:** EDX micrograph of titania nanostructures hydrothermally prepared at (a) 0.25 M (2D platelets), (b) 0.5 M (2D platelets + 1D nanorods mixture), (c) 1.0 M (1D nanorods) and (d) 5.0 M KOH solutions (1D nanofibers). Insets represent the corresponding elemental composition.



**Figure S4:** Equivalent circuit representation of Ti-TiO<sub>2</sub> nanostructured electrode.  $R_{\Omega}$ : Resistance of the active medium (electrolyte),  $R_E$ : Charge flow resistance across Ti-TiO<sub>2</sub> interface,  $R_{ct}$ : Charge transfer resistance across TiO<sub>2</sub>-Electrolyte interface,  $C_E$ : Capacitance of TiO<sub>2</sub>, including surface states and Helmholtz double layer,  $CPE$ : Constant Phase Element defined by  $CPE-T$  {electrostatic capacitance, (in Farad)} and  $CPE-P$  {a fitting parameter,  $\alpha$ , indicating the degree of deviation from a certain state, (dimensionless)}. For  $\alpha = 0, 1, -1$ , the  $CPE$  represents pure resistor, capacitor and inductor, respectively. For  $\alpha \approx 0.5$ , the  $CPE$  corresponds to Warburg impedance,  $W$  [1-3].

**Table S2** EIS fitted data for all the samples according to the equivalent circuit shown in Fig. S4.

<b>Samples</b>	<b><math>R_{\Omega}</math></b> (ohm)	<b><math>C_E</math></b> ( $\mu$ F)	<b><math>R_E</math></b> (ohm)	<b><math>R_{ct}</math></b> (ohm)	<b><math>CPE</math></b> ( $\mu$ F)	<b><math>\alpha</math></b>
<b>0.25M-TO</b> (2D platelets)	2.11	66.5	753.1	9.56	6.99	0.62
<b>0.5M-TO</b> (2D platelets + 1D nanorods)	2.24	72.6	328.9	7.83	1.45	0.57
<b>1.0M-TO</b> (1D nanorods)	7.87	96.7	405.3	12.47	2.01	0.53
<b>5.0M-TO</b> (1D nanofibers)	4.63	208.7	676.6	12.09	2.96	0.50

## References

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3. Y. Xie, L. Zhou, J. Lu, *J Mater Sci* (2009) 44:2907–2915.